

MODIFIED PHOTOLITHOGRAPHY MOVEMENT SYSTEM

Abstract

Attorney Docket No. 22397.324A method and system is provided for moving a substrate relative to a pixel panel in a digital photolithography system. The method can be used for performing photolithography on a substrate, the substrate having a first portion with a first design resolution and a second portion with a second design resolution. The method includes scanning the first portion of the substrate, having the first design resolution, at a first speed and scanning the second portion of the substrate, having the second design resolution, at a second speed, different from the first.

10064156-061403

Figures

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